

IN THE CLAIMS:

Please amend claims 16, 17, 27, 28, 33 and 34, cancel claims 32 and 38, and add new claims 47-51 as follows:

Claims 1-15 (Canceled)

16. (Currently Amended) A cleaning method of ~~manufacturing~~ an electro-optical device comprising:

irradiating a component provided in a film-forming chamber with ~~at least one~~ a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a vapor deposition material adhering to the component; and
exhausting the sublimated vapor deposition material,
wherein the vapor deposition material comprises an organic light emitting material.

C 1. 17. (Currently Amended) A cleaning method of ~~manufacturing~~ a light emitting device comprising:

irradiating a component provided in a film-forming chamber with ~~at least one~~ a light selected from the group consisting of infrared light, UV-light, and visible light, thereby sublimating a vapor deposition material adhering to the component; and
exhausting the sublimated vapor deposition material,
wherein the vapor deposition material comprises an organic light emitting material.

Claims 18-26 (Canceled)

27. (Currently Amended) The method according to claim 16, wherein said ~~at least one~~ light selected from the group consisting of the infrared light, UV-light, and visible light is radiated by using a light source provided in the film-forming chamber.

28. (Currently Amended) The method according to claim 16, wherein an irradiation surface of said ~~at least one~~ light selected from the group consisting of the infrared light, UV-light, and visible light is in a rectangular or oblong shape.

29. (Previously Added) The method according to claim 16 further comprising a step of supplying a halogen containing gas into the film-forming chamber during sublimating the vapor deposition material.

30. (Previously Added) The method according to claim 16 further comprising a step of forming a plasma during exhausting.

31. (Previously Added) The method according to claim 21 wherein said plasma is an oxygen plasma.

Claim 32 (Canceled)

01 33. (Currently Amended) The method according to claim 16, wherein said ~~at least one~~ light selected from the group consisting of the infrared light, UV-light, and visible light is radiated by using a light source provided in the film-forming chamber.

34. (Currently Amended) The method according to claim 16, wherein an irradiation surface of said ~~at least one~~ light selected from the group consisting of the infrared light, UV-light, and visible light is in a rectangular or oblong shape.

35. (Previously Added) The method according to claim 17 further comprising a step of supplying a halogen containing gas into the film-forming chamber during sublimating the vapor deposition material.

02 36. (Previously Added) The method according to claim 17 further comprising a step of forming a plasma during exhausting.

37. (Previously Added) The method according to claim 27 wherein said plasma is an oxygen plasma.

Claim 38 (Canceled)

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Claims 39-46 (Withdrawn)

Please add new claims 47-51 as follows:

47. (New) A cleaning method of an electro-optical device comprising:
irradiating a component provided in a film-forming chamber by scanning a lamp light
source, thereby sublimating a vapor deposition material adhering to the component; and
exhausting the sublimated vapor deposition material,
wherein the vapor deposition material comprises an organic light emitting material.

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48. (New) The method according to claim 47, wherein the lamp light source is
selected from the group consisting of infrared light, UV-light, and visible light.

49. (New) The method according to claim 47, further comprising a step of
supplying a halogen containing gas into the film-forming chamber during sublimating the
vapor deposition material.

50. (New) The method according to claim 47, further comprising a step of
forming a plasma during exhausting.

51. (New) The method according to claim 47, wherein said plasma is an oxygen
plasma.